

SPECIFICATION

E2100300 -v3

Drawing No Rev. Group

Sheet 1 of 2

Blank Material, Silicon Test Mass (ETM/ITM), 40m Mariner

Authors	Date	Document Change Notice, Release or Approval	
R Adhikari, C Wipf		See DCC record	

Requirements

Physical dimensions Right circular cylinder: 150 mm × 150 mm ∅

Clear aperture Central 30 mm diameter

Material Monocrystalline silicon, float zone

Dopants Undoped; best effort for minimal residual dopant contamination

Resistivity $> 30 \text{ k}\Omega$ cm; radial variation and striation $\pm 20\%$ in clear aperture

Interstitial oxygen < 10¹⁶/cm³

Micro defects Voids only; density $< 10^3/\text{cm}^3$

Bubbles/inclusions Total cross section in clear aperture is < 10000 square micrometers

No bubbles > 100 micron diameter; disregard bubbles < 10 micron diameter

Crystal orientation Flat surfaces of cylinder aligned with {100} crystal plane, ±1°

Index homogeneity $\leq 2.5 \times 10^{-6}$ peak-to-valley; $\leq 5 \times 10^{-7}$ peak-to-valley in clear aperture

Birefringence $\leq 5 \text{ nm/cm}$; $\leq 1 \text{ nm/cm}$ in clear aperture

Final shaping Performed using a grit size progression ending with a 320 or smaller grit tool

Defect depth < 0.5 mm on any surface or corner

Serial number Serialized as TMXX, where XX increments starting at 01



SPECIFICATION

 $\begin{array}{ccc} E2100300 & -v3 \\ \\ \text{Drawing No} & \text{Rev. Group} \end{array}$

Sheet 2 of 2

Blank Material, Silicon Test Mass (ETM/ITM), 40m Mariner

Specification	Method	Inspection Frequency	Data Delivered
Physical dimensions	Inspection	100%	Certification
Material	Process control Material certification	100%	Certification
Dopants	Process control Material certification	100%	Certification
Resistivity	Process control Material certification	100%	Certification
Interstitial oxygen	Process control Material certification	100%	Certification
Micro defects	Process control Material certification	100%	Certification
Bubbles/inclusions	Infrared imaging	100%	Hand sketch indicating location and dimensions
Crystal orientation	Process control Material certification	100%	Certification
Index homogeneity	Interferometric measurement	100%	Inspection report included with certification
Birefringence	Infrared polariscope	100%	Inspection report included with certification
Defect depth	Visual inspection	100%	Certification
Serial number	Visual inspection	100%	Certification

Table 1: MEASUREMENT MATRIX: FREQUENCY AND METHOD